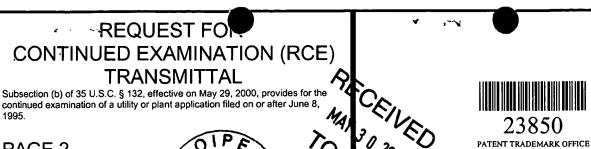
REQUEST FOR
CONTINUED EXAMINATION (RCE)
TRANSMITTAL
Subsection (b) of 35 U.S.C. § 132, effective on May 29, 2000, provides for the continued
Subsection (b) of 35 U.S.C. § 132, effective on May 20, 2000, provides for the continued and the subsection of a utility or plant application flet on branching up 8, 1995.
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TC 1700

Application Number	09/622,615		
Filing Date	August 18, 2000		
First Named Inventor	NOGAMI, et al.		
Group Art Unit	1745		
Name of Examiner	Julian A.Mecado		
Agent Docket No.	000774		

This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application.

Note: 37 C.F.R. §1.114 is effective on May 29, 2000. If the above-identified application was filed prior to May 29, 2000, applicant may wish to consider filing a continued prosecution application (CPA) under 37 C.F.R. §1.53 (PTO/SB/29) Instead of a RCE to be eligible for the patent term adjustment provisions of the AIPA. See changes to Application Examination and Provisional Application Practice, Interim Rule, 65 Fed. Reg. 14865 (Mar 20, 2000) 1233 Off. Gazette Pat

1.	Sub	miss	sion Required Under 37 C.F.R. § 1.114	
a.	□ Previously submitted			
	i.		Consider the amendment(s)/reply under 37 C.F.R. §1.116 previously filed on (Any unentered amendment(s) referred to above will be entered)	
	ii.		Consider the arguments in the Appeal Brief or Reply Brief previously filed on	
	iii.		Other	
b.	⊠ i.	Ei ⊠	05/29/2003 DTESSEM1 00000076 09622615 01 FC:1801 750.00 ()P	
	ii.		Affidavit(s)/Declaration(s)	
	iii.		. ,	
	iv.	×	Other Petition for Extension of Time	
2.	Mis	scella	aneous	
a.	□ Suspension of Action on the above-identified application is requested under 37 C.F.R. §1.103(c) for a period o months (period shall not exceed three months; Fee under 37 C.F.R. §1.17(i) required)			
b.	□ o ₁	ther _		
3.	Fe	es T	The RCE fee under 37 C.F.R. §1.17(e) is required by 37 C.F.R. §1.114 when the RCE is filed.	
a.			irector is hereby authorized to charge the following fees, or credit any overpayments, to Deposit unt No. 01-2340	
	j. l	□ R	RCE fee required under 37 C.F.R. § 1.17 (e)	
	ii.	□ E	xtension of Time Fee (37 C.F.R. §§ 1.136 and 1.17)	
	iii.	□ o	Other	
b.	X	Check	k in the amount of \$1,160.00 is enclosed. \$750.00 for filing fee and \$410.00 extension fe	



PAGE 2





Atty Docket No.

000774

SIGNATURE BY APPLICANT, ATTORNEY, OR AGENT REOUIRED

Name

Daniel A. Geselowitz, Ph.D.

42,573 (agent) Registration No.

Signature



Date May 27, 2003

CERTIFICATE OF MAILING OR TRANSMISSION

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner for Patents, MAIL STOP RCE, Washington, D.C. 20231, or facsimile transmitted t the U.S. Patent and Trademark Office on:

Name

Signature

RECEIVED MAY 3 0 2003

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: NOGAMI, et al.

Examiner: Julian A. Mercado

Group Art Unit: 1745

Serial No.: 09/622,615

Filed: August 18, 2000

P.T.O. Confirmation No.: 7364

For.

NICKEL ELECTRODE FOR ALKALINE STORAGE BATTERY, METHOD OF PRODUCING NICKEL ELECTRODE FOR ALKALINE STORAGE BATTERY,

AND ALKALINE STORAGE BATTERY

AMENDMENT ACCOMPANYING REQUEST FOR CONTINUED EXAMINATION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

May 27, 2003

Sir:

This is a Amendment for the above-captioned patent application. Please amend the above-captioned patent application as follows:

CLEAN VERSION OF AMENDMENTS

IN THE CLAIMS:

Please cancel claims 12-18 and 25 without prejudice or disclaimer.

Please amend claims 1 and 2 as follows:

1. (Twice Amended) A sintered nickel electrode for an alkaline storage battery in which an active material mainly containing nickel hydroxide is applied to a porous sintered nickel substrate, characterized in that a coating layer containing at least one hydroxide of an element selected from the group consisting of strontium Sr, scandium Sc, yttrium Y, the lanthanoid elements, and bismuth Bi is formed only on a surface that contacts with an electrolyte solution of the active material formed on the porous sintered nickel substrate.

